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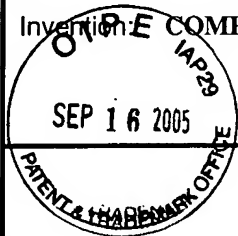
December 22, 2004

Examiner

WU, Ives J.

Group Art Unit

1713

Invention: **COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME**I hereby certify that this English Language abstract of JP 62-062521 - 1 Page

(Identify type of correspondence)

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PATENT ABSTRACTS OF JAPAN

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(21)Application number : 60-201525 (71)Applicant : HITACHI LTD

(22)Date of filing : 13.09.1985 (72)Inventor : TANAKA TOSHIHIKO

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(54) PATTERN FORMING METHOD

(57)Abstract:

PURPOSE: To form an ultrafine and accurate pattern and a pattern having high alignment accuracy by forming a film made of polysaccharide on a resist before exposing.

CONSTITUTION: Polysaccharide is formed on a photoresist film or an X-ray resist film. The polysaccharide is transparent, and has smaller refractive index than that of the resist. Therefore, it serves as a resist reflection preventive film. Since dimensional accuracy and alignment accuracy can be improved, a circuit can be integrated, a chip area can be contracted, and a high quality element having stable electric characteristic can be obtained at a high yield.

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